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Understanding the electron transport mechanisms in MoO_x-based layer stack for application in simplified IBC-SHJ solar cells

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Silicon heterojunction (SHJ) solar cells



Simple processing and controlable high shunt resistance?

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H. Lin, et al., *Nat. Energy*, **8**, 789 (2023)
 H. Wu, et al., *Nature*, **635**, 604 (2024)
 A. Tomasi, et al., *Nat. Energy*, **2**, 17062 (2017)
 D. Lachenal, bifiPV Workshop, Zhuhai, China (2024)

Alternative material choice



• η = 23.83% FBC-SHJ solar cell with ~2 nm MoO_x as HTL ^[4]

Potentially faster processing of blanket layer

Novel ETL with (n)nc-Si:H and MoO_x^[2, 5]

[1] A. Tomasi, et al., *Nat. Energy*, 2, 17062 (2017)
 [2] K. Kovačević, et al., *Prog. Photovolt. Res. Appl*, (2024)
 [4] L. Cao, et al., *Prog. Photovolt. Res. Appl*, 31, 1245 (2022)
 [3] L. Gerling, et al., *Sol. Energ. Mater. Sol. Cells*, 145, 109 (2016)
 [5] K. Kovačević, et al., *To be submitted*



Working principle of the electron transport layer (ETL) stack



Charge transfer in conduction band and no recombination junction





n-type c-Si





- Optimization of electron transport layer (ETL) stack
- Understanding of charge carrier collection
 - Effect of temperature
 - Interface analysis

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 $\eta > 23\%$

[1] L. Mazzarella, et al., *Prog. Photovolt. Res. Appl*, **29**, 391 (2020)
[2] L. Cao, et al., *Prog. Photovolt. Res. Appl*, **31**, 1245 (2022)

ETL contact stack evaluation



Experimental evaluation of passivation and transport

Plasma treatment (PT) SiH₄, H₂, CO₂^[2]

and plasma treatment with boron (PTB) SiH_4 , H_2 , CO_2 , B_2H_6 ^[2, 3]



(*n*)nc-Si:H thickness

TUDelft 7 All FBC-SHJ solar cells feature ITO TCO and screen-printed Ag contact

[1] Y. Zhao, et al., Sol. Energ. Mater. Sol. Cells, 219, 110779 (2021)

- [2] L. Cao, et al., Prog. Photovolt. Res. Appl, 31, 1245 (2022)
- [3] L. Mazzarella, et al., Prog. Photovolt. Res. Appl, 29, 391 (2020)

ETL contact stack evaluation





Improved FF from

(n)nc-Si:H/MoO_x

• Overall improvement with PTB and lower sensitivity to (*n*)nc-Si:H thickness

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*Based on results of high-resolution transmission electron microscopy **TUDelft** 10 (HR-TEM) and energy-dispersive X-ray spectroscopy (EDX) analysis

Future optimization towards $\eta > 24\%$

- Passivation enhancement
- (*n*)nc-Si:H improvement
- Double layer anti-reflection coating
- Metal grid redesign for higher bifaciality

Conclusion

- Optimization of electron transport layer (ETL) stack
- Understanding of charge carrier collection
 - Effect of temperature
 - Interface analysis

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Thank you for your attention!

Contact

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